

# Power Dissipation

## CMOS VLSI Design

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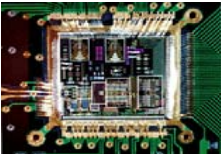


# Outline of the Talk

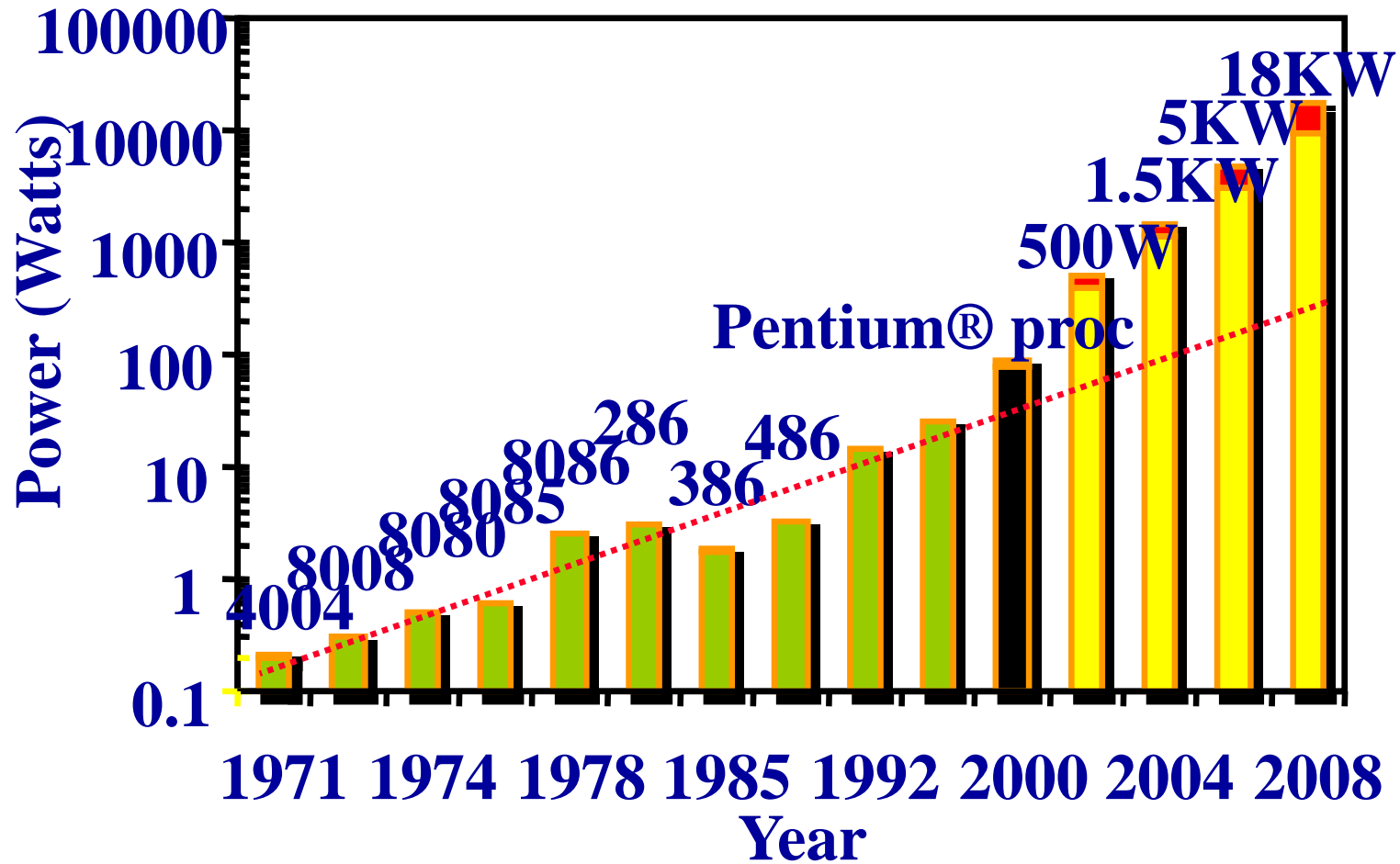
- Power and Energy
- Dynamic Power
- Static Power
- Low Power Design



# Power Dissipation Trend



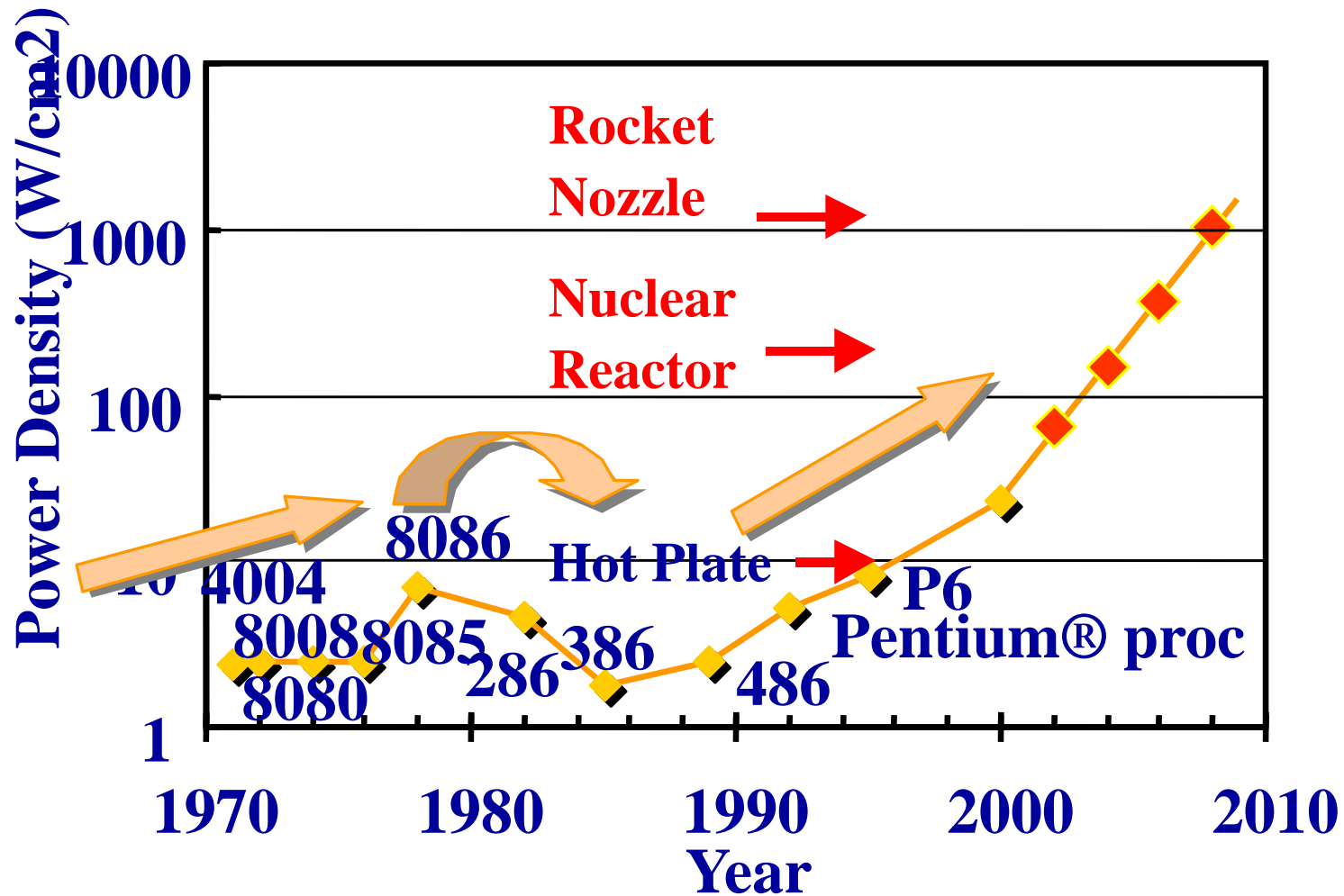
# Power Dissipation Trend



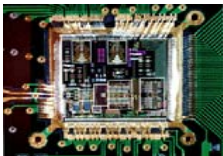
Power delivery and dissipation will be prohibitive



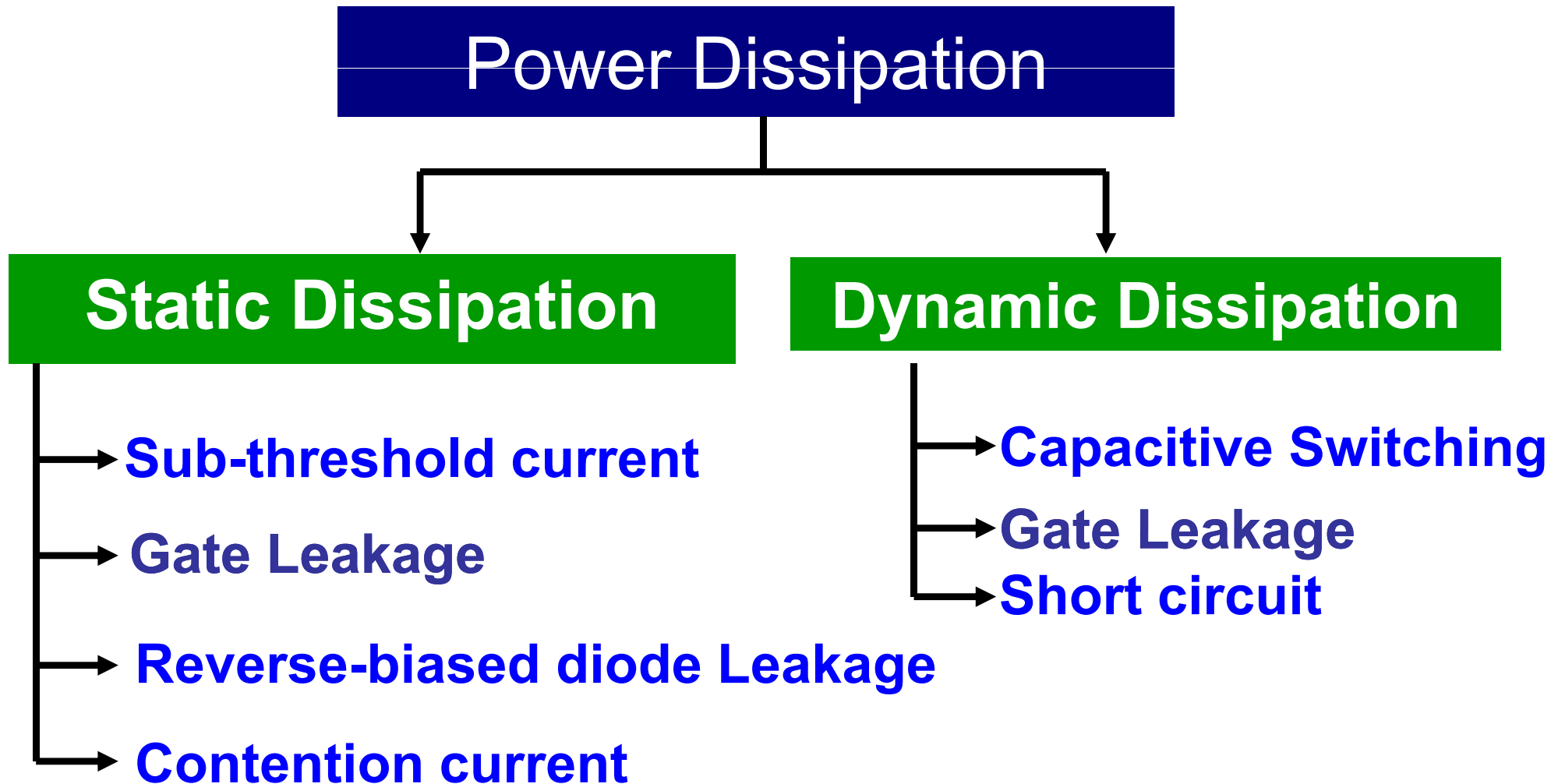
# Power density Trend



Power density too high to keep junctions at low temp



# Power Dissipation in CMOS

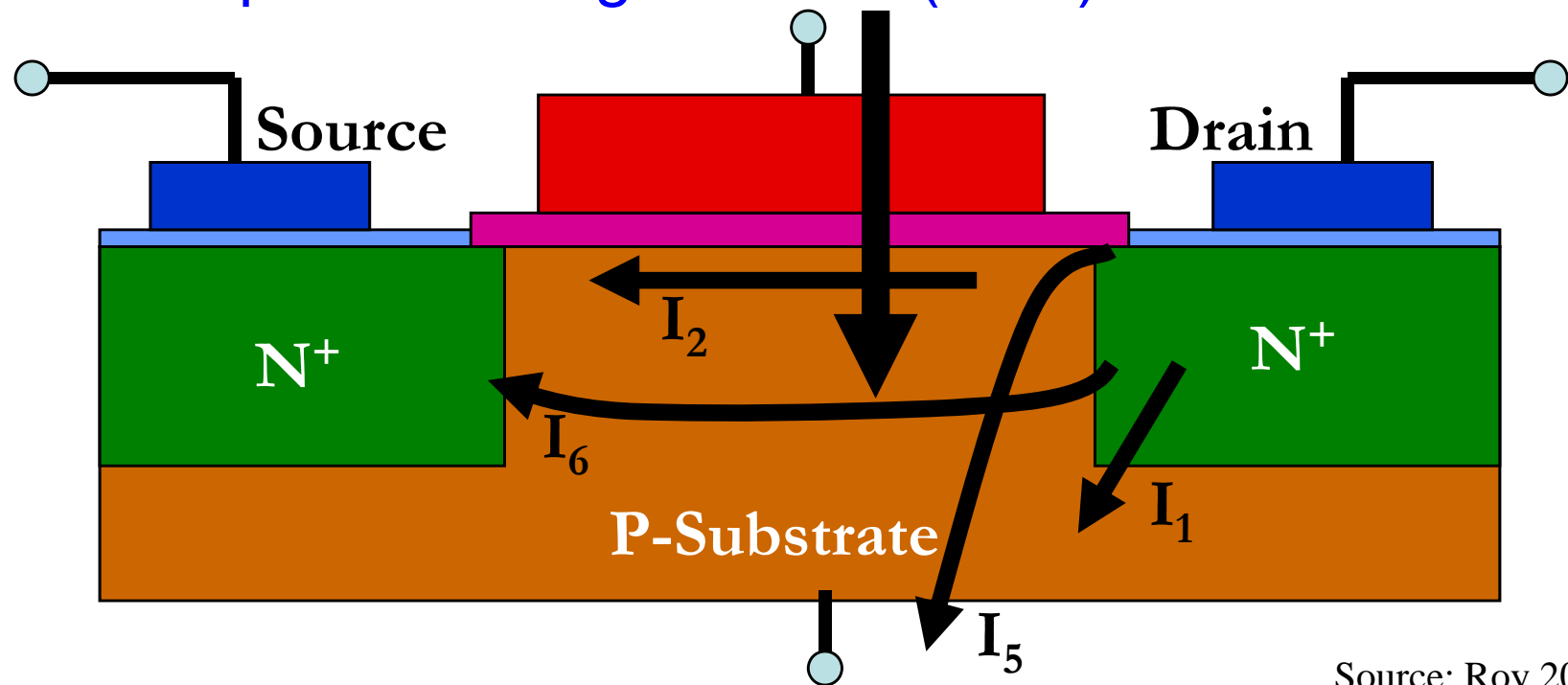


Source: Weste and Harris 2005

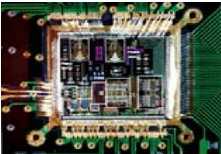


# Leakages in CMOS

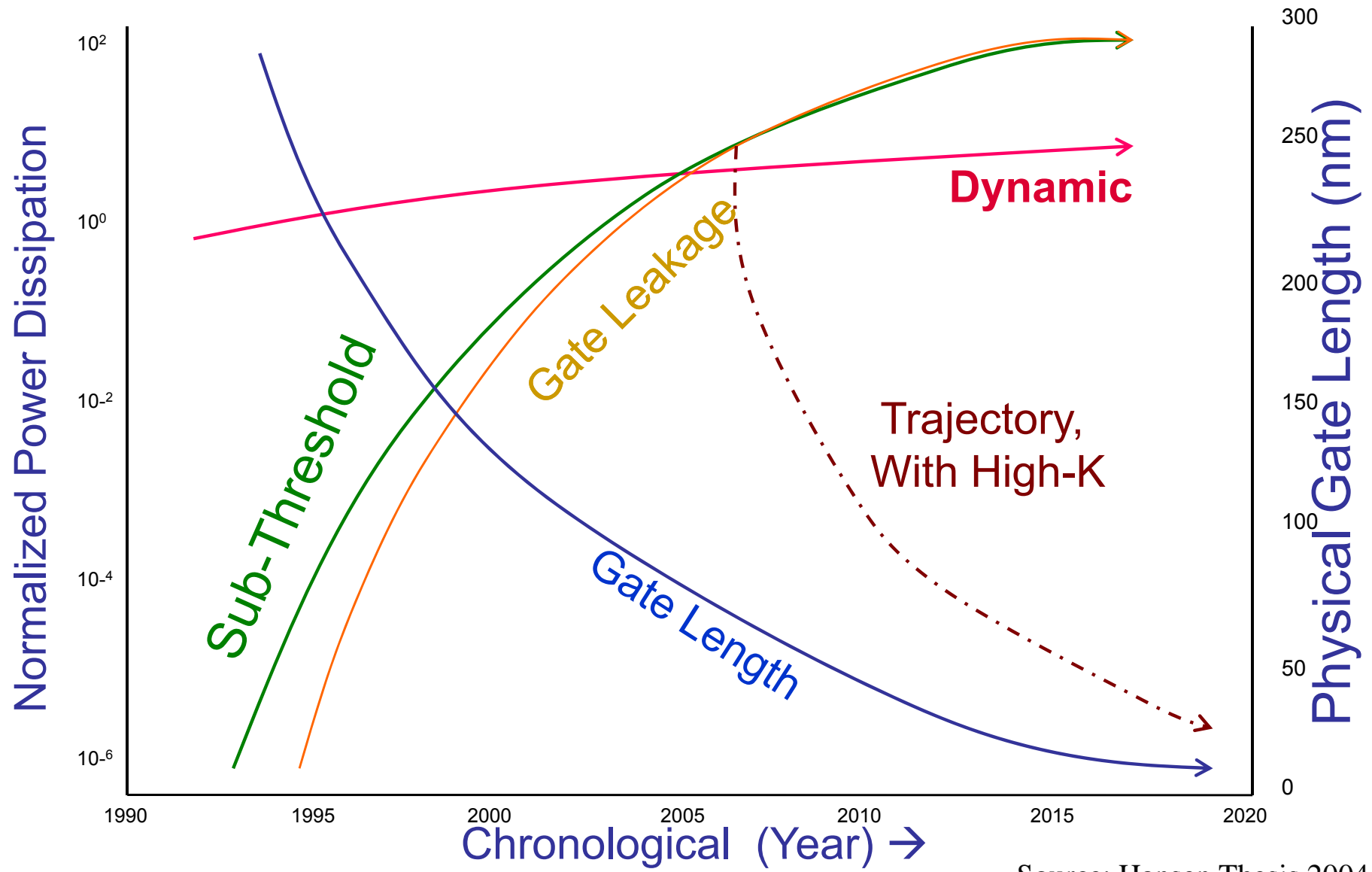
- $I_1$  : reverse bias pn junction (both ON & OFF)
- $I_2$  : subthreshold leakage (OFF )
- $I_3$  : Gate Leakage current (both ON & OFF)
- $I_4$  : gate current due to hot carrier injection (both ON & OFF)
- $I_5$  : gate induced drain leakage (OFF)
- $I_6$  : channel punch through current (OFF)



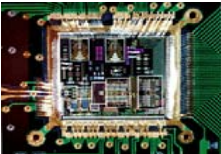
Source: Roy 2003



# Power Dissipation Redistribution

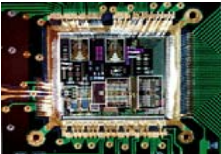


Source: Hansen Thesis 2004





# Dynamic and Static Power Sources



# Power Dissipation in CMOS : Dynamic

**Capacitance Switching Current:** This flows to charge and discharge capacitance loads during logic changes.

**Short-Circuit Current:** This is the current due to the DC path between the supply and ground during output transition.

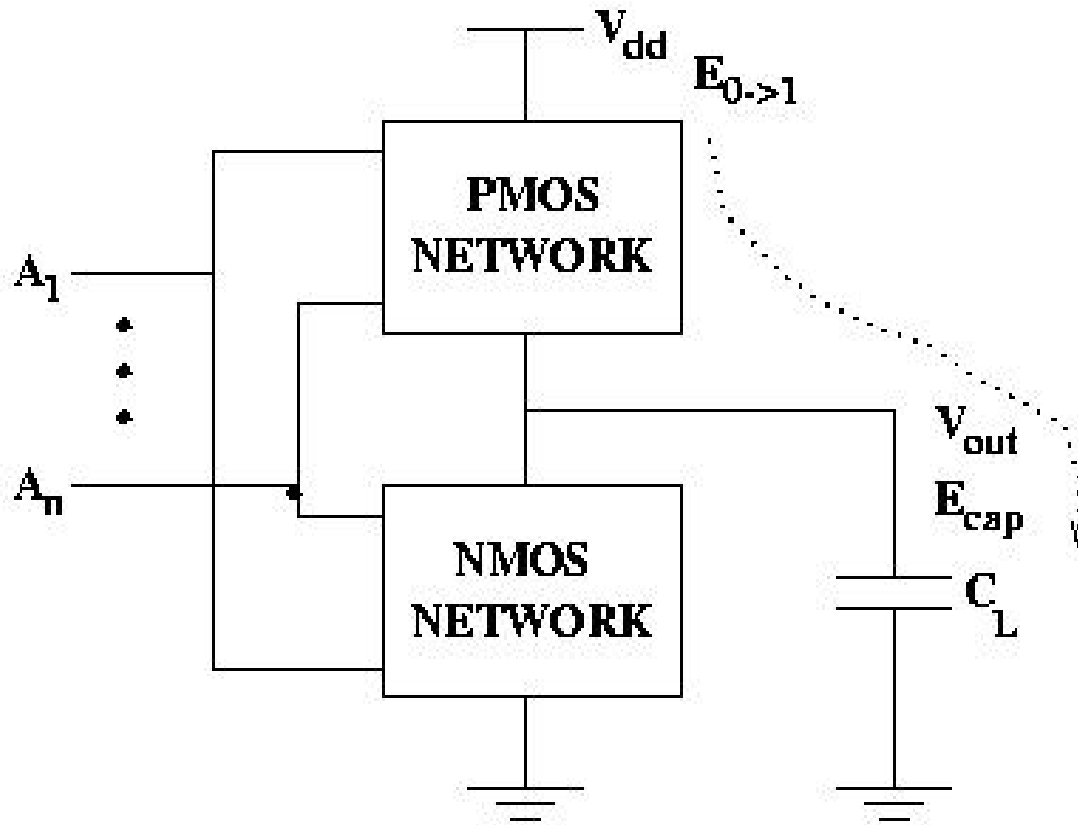


# Power Dissipation in CMOS : Static

- **Subthreshold Current:** Sub-threshold current that arises from the inversion charges that exists at the gate voltages below the threshold voltage.
- **Tunneling Current:** There is a finite probability for carrier being pass through the gate oxide. This results in tunneling current thorough the gate oxide.
- **Reverse-biased Diode Leakage:** Reverse bias current in the parasitic diodes.
- **Contention Current in Ratioed Circuits:** Ratioed circuits burn power in fight between ON transistors



# Power Dissipation in CMOS : Dynamic



A general CMOS transistor circuit

- Dynamic power is required to charge and discharge load capacitances when transistors switch.
- One cycle involves a rising and falling output.
- On rising output, charge  $Q = CLVDD$  is required.
- On falling output, charge is dumped to GND.



# Power Dissipation in CMOS : Dynamic

$$E_{0 \rightarrow 1} = \int_0^T P(t) dt = V_{dd} \int_0^T i_{\text{supply}}(t) dt = V_{dd} \int_0^{V_{dd}} C_L dV_{\text{out}} = C_L V_{dd}^2$$

$$E_{\text{out}} = \int_0^T P_{\text{out}}(t) dt = \int_0^T V_{\text{out}} i_{\text{out}}(t) dt = \int_0^{V_{dd}} C_L V_{\text{out}} dV_{\text{out}} = \frac{1}{2} C_L V_{dd}^2$$

Note:

1. the difference between the two is the loss
2. Energy doesn't depend on frequency



# Power Dissipation in CMOS : Dynamic

For  $N_c$  clock cycles energy loss :

$$E_{N_c} = C_L V_{dd}^2 n(N_c)$$

$n(N_c)$  : is the number of 0->1 transitions in  $N_c$  clock cycles

$$P_{avg} = \lim_{N \rightarrow \infty} \left[ \frac{E_{N_c}}{N_c} \right] f = \left[ \lim_{N \rightarrow \infty} \frac{n(N_c)}{N_c} \right] C_L V_{dd}^2 f$$
$$= \alpha_{0 \rightarrow 1} C_L V_{dd}^2 f$$

Note: Power depends on frequency



# Short Circuit Current

- When transistors switch, both nMOS and pMOS networks may be momentarily ON at once.
- Leads to a blip of “short circuit” current.
- $< 10\%$  of dynamic power if rise/fall times are comparable for input and output.



# Static Power : Subthreshold Current

- In OFF state, undesired leakage current flow.
- It contributes to power dissipation of idle circuits.
- Drain-Induced-Barrier-Lowering (DIBL) an prominent effect for short channel transistors also impacts subthreshold conduction by lowering  $V_T$ .
- This current increases as the  $V_T$  increases.
- It also increases as the temperature increases.
- If  $v_t$  is the thermal voltage and  $I_0$  is the current at  $V_T$  then the subthreshold current is :

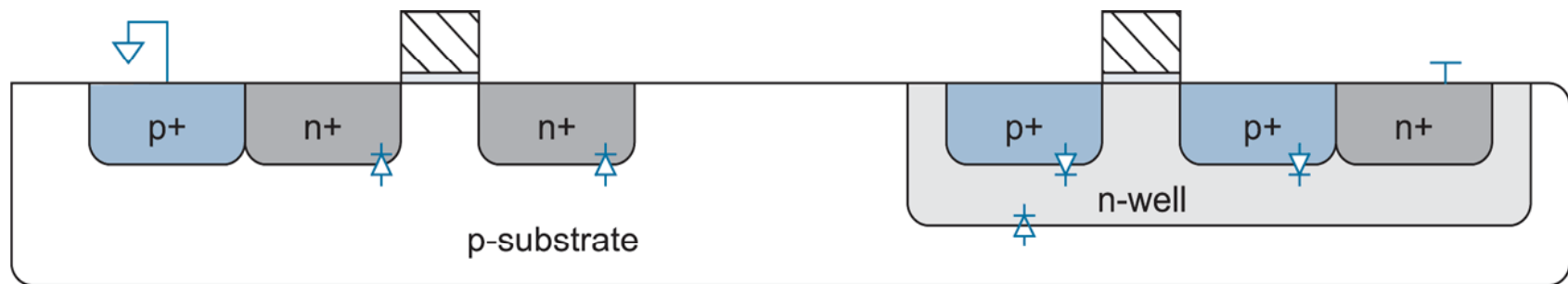
$$I_{ds} = I_0 \left[ 1 - \exp\left(-\frac{V_{ds}}{v_t}\right) \right] \cdot \exp\left(\frac{V_{gs} - V_{th} - V_{off}'}{n v_t}\right)$$



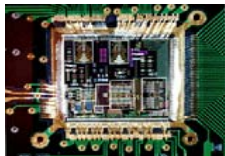


# Static Power : Junction Leakage

- The pn junctions between diffusion, substrate and well are all junction diodes.
- These are reversed biased as substrate is connected to GND and well connected to  $V_{dd}$ .
- However, reversed biased diode also conduct small amount of current.



Reverse-biased diodes in CMOS circuits



# Static Power : Junction Leakage

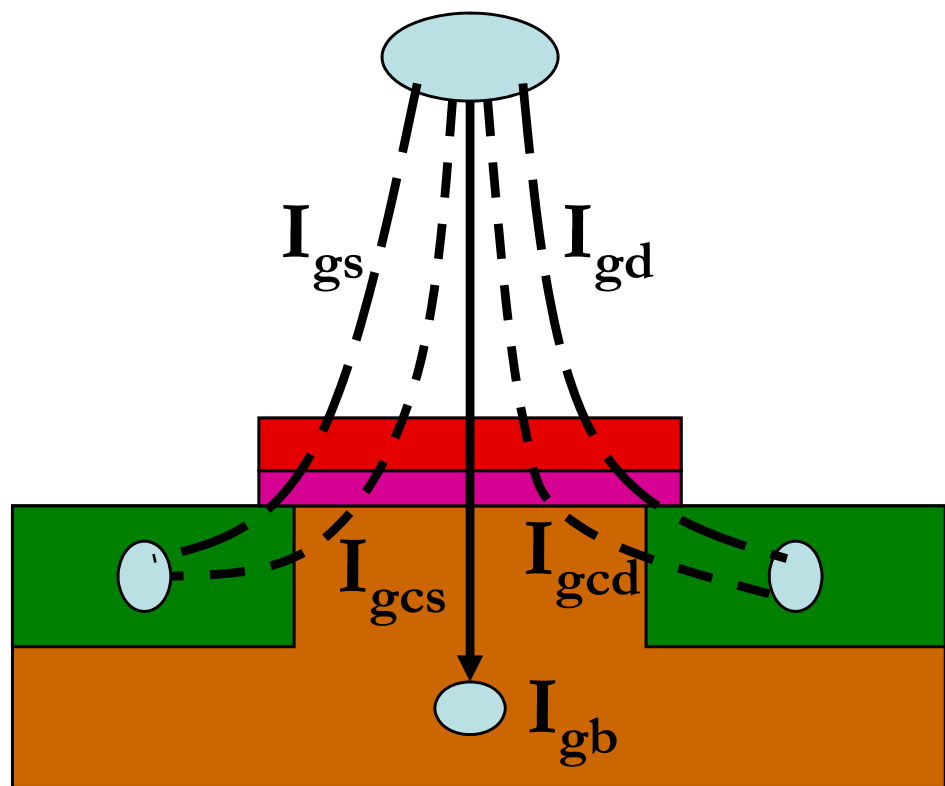
- The reverse-biased junction current is expressed as follows: (D is not for drain, S is not for source)

$$I_D = I_S [ \exp (V_D/v_T) - 1 ]$$

- $I_S$  depends on the doping level, the area, and perimeter of the diffusion region.
- $V_D$  is the diode voltage e.g.  $V_{sb}$  or  $V_{db}$ .



# Static Power : Tunneling



BSIM4 Model

- There is a finite probability for carrier being pass through the gate oxide.
- This results in tunneling current thorough the gate oxide.
- The effect is predominate for lower oxide thickness.



# Static Power : Tunneling

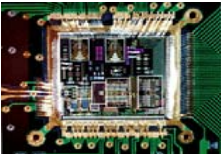
- The gate oxide leakage current can be expressed as follows [Kim2003, Chandrakasan2001] (K and  $\alpha$  are experimentally derived factors).

$$I_{\text{gate}} = K W_{\text{gate}} (V_{\text{dd}} / T_{\text{gate}})^2 \exp(-\alpha T_{\text{gate}} / V_{\text{dd}})$$

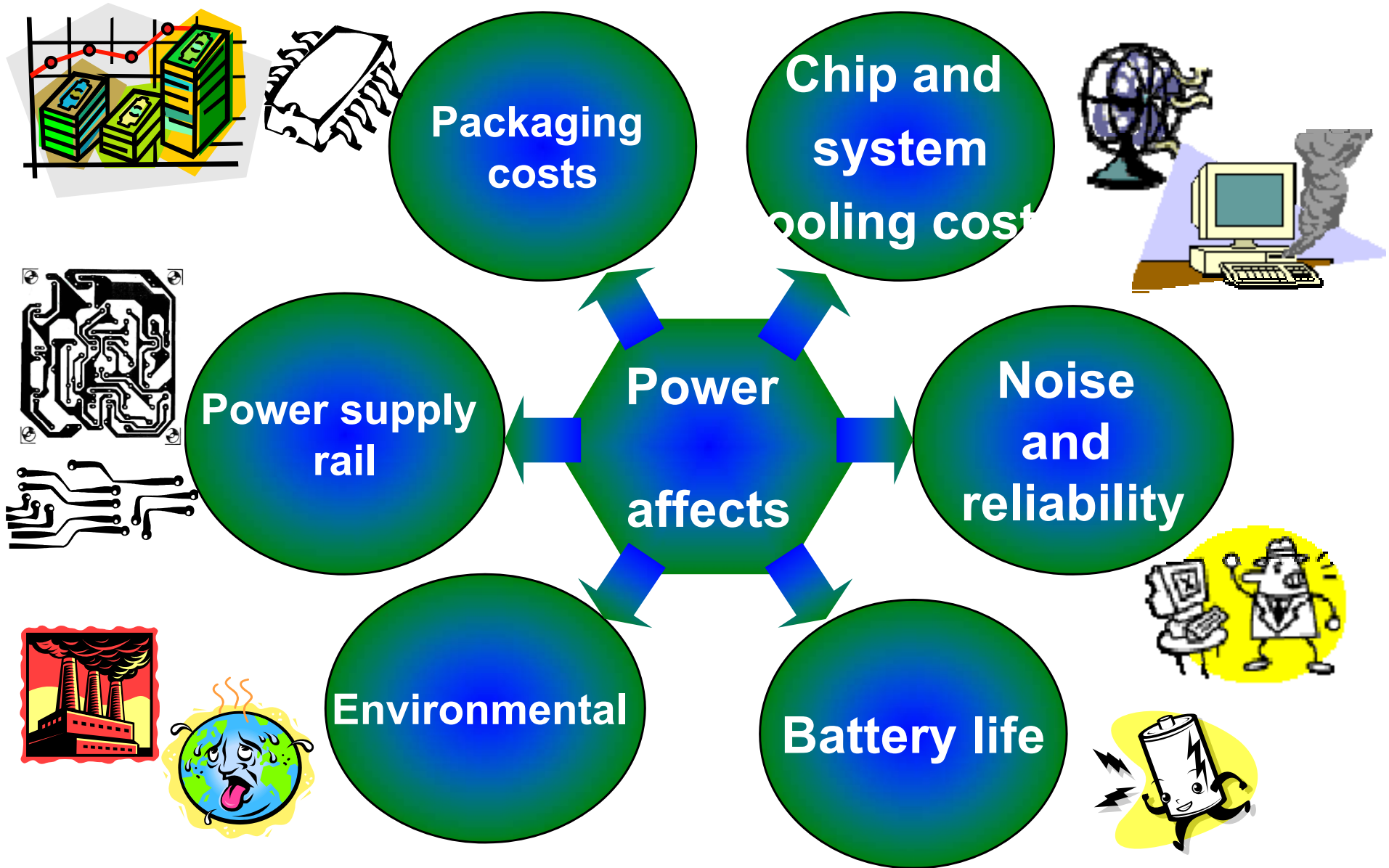
- **Options for reduction of gate leakage power :**
  - Decreasing of supply voltage  $V_{\text{dd}}$  (will play its role)
  - Increasing gate  $\text{SiO}_2$  thickness  $T_{\text{gate}}$  (opposed to the technology trend !!)
  - Decreasing gate width  $W_{\text{gate}}$  (only linearly dependent)



# Low-Power Design



# Why Low Power?



# Various forms of Power Profile

- Average Power
- Total Energy
- Energy-Delay-Product (EDP)
- Power-Delay-Product (PDP)
- Power-Square-Delay-Product (PSDP)
- Peak Power
- Transient Power
- Cycle Difference Power
- Peak Power Differential
- Cycle-to-Cycle Power Gradient (Fluctuation)
- and many more .....



# Why peak power reduction ?

- To maintain supply voltage levels
- To increase reliability
- To use smaller heat sinks
- To make packaging cheaper





# Why Average Power/ Energy reduction ?

- To increase battery life time
- To enhance noise margin
- To reduce energy costs
- To reduce use of natural resources
- To increase system reliability



# Why Transience / Fluctuation Minimization ?

- To reduce power supply noise
- To reduce cross-talk and electromagnetic noise
- To increase battery efficiency
- To increase reliability



# Low-power design: Key Principles

- using the lowest possible supply voltage
- using the smallest geometry, highest frequency devices, but operating them at lowest possible frequency
- using parallelism and pipelining to lower required frequency of operation
- power management by disconnecting the power source when the system is idle



# Voltage, Frequency and Power Trade-offs

- **Reduce Supply Voltage ( $V_{dd}$ ):** delay increases; performance degradation
- **Reduce Clock Frequency ( $f$ ):** only power saving no energy
- **Reduce Switching Activity ( $N$  or  $E(sw)$ ):** no switching no power loss !!! Not in fully under designers control. Switching activity depends on the logic function. Temporal/and spatial correlations difficult to handle.
- **Reduce Physical Capacitance:** done by reducing device size reduces the current drive of the transistor making the circuit slow



# How much we save ?? Varying $V_{dd}$ / $f$

Voltage ( $V_{dd}$ )	Frequency ( $f$ )	Power ( $P_d$ )	Energy ( $E_d$ )
$V_{dd}$	$f_{max}$	$P_d$	$E_d$
$V_{dd} / 2$	$f_{max}^*$	$P_d / 4$	$E_d / 4$
$V_{dd} / 2$	$f_{max} / 2$	$P_d / 8$	$E_d / 4$
$V_{dd}$	$f_{max} / 2$	$P_d / 2$	$E_d$

\* Note :  $f_{max} \propto V_{dd}$



# Low Power Design : Static Reduction

- Reduce static power
  - Selectively use ratioed circuits
  - Selectively use low  $V_t$  devices
  - Leakage reduction:  
stacked devices, body bias, low temperature

